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Min-Su Pang, et al.

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Examiner Initial		Document No.	Date	Name	Class	Subclass	Filing Date if Appropriate
VN	A	4,236,165	4/1982	Szedon			
VN	B	4,812,756	3/1989	Curtis, et al.			
VN	C	5,216,362	6/1993	Verkuil			
VN	D	5,498,974	3/1996	Verkuil, et al.			
VN	E	5,767,693	6/1998	Verkuil			
VN	F	5,834,941	11/1998	Verkuil, et al.			
	G						
	H						

		Document No.	Date	Country	Class	Subclass	Translation
	I						
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		Document No.	Date	Country	Class	Subclass	Translation
VN	K	Solid State Technology, Test/Measurement, "Monitoring Electrically Active Contaminants to Assess Oxide Quality", Gregory S. Horner, et al., June 1985, PennWell Publishing Company, 4 Pages.					
VN	L	Semiconductor International, "A New Approach for Measuring Oxide Thickness", Tom G. Miller, July 1995, Cahners Publishing Company, 2 Pages.					
VN	M	"COS Testing Combines Expanded Charge Monitoring Capabilities with Reduced Costs", Michael A. Peters, Semiconductor Fabtech 95, 4 Pages.					
VN	N	Process Monitoring, "Corona Oxide Semiconductor Test", Semiconductor Test Supplement, February/March 1995, Pages S-3 and S-5.					
VN	O	"Quantox™ Non-Contact Oxide Monitoring System", John Bickley, 1995 Keithley Instruments, Inc., No. 1744, 6 Pages. (month unavailable)					

Examiner:

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12/09/04

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Initial if reference considered, regardless of whether citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.